

SIMULATION OF SINGLE ELECTRON TRANSISTOR (SET)
CIRCUITS USING MONTE CARLO METHOD

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ABSTRACT

The very fast switching characteristics and very low power consumption have given the single electron transistor (SET) promising capabilities to replace CMOS transistors in some semiconductor applications. SET theory of operation is now well established nevertheless the transistor is still under laboratory investigations in the fields of fabrication and applications in Large Scale Integration (LSI). Simulation of SET consumes a great deal of computer time, which arises a need to renovate fast and accurate simulation algorithms. This paper presents a simple model for SET circuits, based on the orthodox theory, which calculates carrier transfer rates from source to drain of the transistor by utilizing statistical mechanics. The simulator that is used for this project is MOSES version 1.2 (Monte Carlo Single Electron Transistor Simulator) which has been developed by Ruby Chen in Year 1997. The reason for choosing this program is because it is free and sufficient to simulate SET circuits such as Array, Junction and SET.

ABSTRAK

Ciri pensuisan pantas dan penggunaan kuasa yang rendah menjadikan SET sebagai pesaing utama bagi CMOS di dalam industri semikonduktor. Walaupun teknologi ini masih di peringkat kajian makmal bagi menyelesaikan isu fabrikasi dan Integrasi Skala Besar (LSI), namun teori tentang bagaimana SET beroperasi telah diterima ramai. Simulasi SET melibatkan masa pemprosesan komputer yang lama, oleh itu algoritma yang efficient harus diguna pakai. Kertas projek ini membentangkan model litar SET yang ringkas berdasarkan teori ortodoks yang mengira kadar pemindahan pembawa dari sumber ke pemungut menggunakan statistik mekanik. Simulator yang digunakan adalah Monte Carlo Single Electron Transistor (MOSES versi 1.2) yang telah dibangunkan oleh Ruby Chen pada tahun 1997. Ianya telah dipilih berdasarkan lesennya yang percuma dan berkesan didalam proses simulasi litar SET seperti Array, Junction dan SET.

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CHAPTER 1

INTRODUCTION

This project studies about the single electron transistor (SET) properties by simulating 3 types of circuits with Monte-Carlo Single Electronics Simulator (MOSES). Single-electron transistor (SET) is a device to amplify current in nanoelectronics. Basically there are three types of SET circuit based on its scale. The first one is tunnel junction which in short is called Junction, is the elementary structure of SET. The second one is the SET itself which consists of 2 tunnel junction. The third one consists of more than one SET (in this project is 21) and is called Array circuit. As explained in Result and Discussion, we can see a tremendous different among this three for IV curve, Spectrum densities and Energy. We also simulate these circuits using different value of external factors such as capacitance and temperatures.

Semiconductor electronics have seen a sustained exponential decrease in size and cost and a similar increase in performance and level of integration over the last thirty years. From computers that take up the entire room to handhelds to embedded computers. George E. Moore, the co-founder of Intel had predicted this in what is known as the Moore's Law.

“The complexity for minimum component costs has increased at a rate of roughly a factor of two per year ... Certainly over the short term this rate can be expected to continue, if not to increase. Over the longer term, the rate of increase is a bit more uncertain, although there is no reason to believe it will not remain nearly constant for at least 10 years. That means by 1975, the number of

components per integrated circuit for minimum cost will be 65,000.

I believe that such a large circuit can be built on a single wafer.”

Although Moore's Law was initially made in the form of an observation and forecast, the more widely it became accepted, the more it served as a goal for an entire industry. This drove both marketing and engineering departments of semiconductor manufacturers to focus enormous energy aiming for the specified increase in processing power that it was presumed one or more of their competitors would soon actually attain. In this regard, it can be viewed as a self-fulfilling prophecy. And Moore's Law is expected to hold for at least the next decade.

Based on Moore's Law, a consortium of integrated circuit manufacturers called the Semiconductor Industry Association (SIA) produced and estimate of how technology is expected to evolve. The following table shows a sample of the SIA roadmap [1].

Year	1999	2001	2004	2006	2009	2012
Transistor gate length	0.14 μm	0.12 μm	90 nm	65 nm	50 nm	35 nm
Transistors per cm^2	14 million	16 million	24 million	40 million	64 million	100 million
Chip size	80 mm^2	850 mm^2	900 mm^2	1000 mm^2	1100 mm^2	1300 mm^2

Table 1: A sample of the SIA Roadmap

The first row of the table indicates that the minimum gate length is expected to reduce steadily to about 35nm by year 2012. The size of transistors determines how many transistors can be placed in a given amount of chip area. We can see the need for smaller transistors, hence the driving force behind the research of SETs.

SETs have been widely studied and demonstrated due to the maturity and variety of their process technologies. These devices based on the single-electron charging effect, i.e., the Coulomb blockade in Si nanostructures, are promising

because their operation principle becomes more robust as the device size is scaled down unlike MOSFET, which will be further explained in the following section. Moreover, their power consumption is quite low. However, SETs are not expected to replace the conventional CMOS logic devices because of their inherent limitations such as a low voltage gain and current drivability. In contrast, new functionalities of SETs, such as quantum cellular automata (QCA), binary decision diagram (BDD) devices, and the multivalued logic, have been explored extensively [2].

1.1 Problems Faced to Scale-down MOSFET

The metal-oxide-semiconductor field-effect transistor (MOSFET, MOS-FET, or MOS FET), is by far the most common field-effect transistor in both digital and analog circuits. The MOSFET is composed of a channel of n-type or p-type semiconductor material, and is accordingly called an NMOSFET or a PMOSFET (also commonly called nMOSFET, pMOSFET, NMOS FET, PMOS FET, nMOS FET, pMOS FET).

The MOSFET has become the basic element of all silicon integrated circuits. The growth of digital technologies like the microprocessor has provided the motivation to advance MOSFET technology faster than any other type of silicon-based transistor. The principal reason for the success of the MOSFET was the development of digital CMOS logic, which uses p- and n-channel MOSFETs as building blocks. The great advantage of CMOS logic is that they allow no current to flow (ideally), and thus no power to be consumed, except when the inputs to logic gates are being switched. CMOS accomplishes this by complementing every nMOSFET with a pMOSFET and connecting both gates and both drains together. A high voltage on the gates will cause the nMOSFET to conduct and the pMOSFET not to conduct and a low voltage on the gates causes the reverse. During the switching time the voltage goes from one state to another and both will conduct. This arrangement greatly reduces power consumption and heat generation.

Overheating is a major concern in integrated circuits, since ever more transistors are packed into ever smaller chips.

The steady reduction in the minimum feature size in integrated circuits has helped the microelectronic industry to produce products with spectacular increase in computational capability and integration density at lower cost. Smaller transistors operate faster than larger ones, and for a given chip technology, the cost of a chip decreases with area rather than with the number of transistors. As scaling down of MOSFET proceeds, we are faced with extremely shallow source and drain (S/D) junctions with low resistances.

As for the CMOS, when its dimension is scaled to the deep nanometer arena, in particular the channel length, the electrical barriers in the device begin to lose their insulating properties due to thermal injection and quantum-mechanical tunneling. This results in a rapid rise of the standby power of the chip, placing a limit on the integration level as well as on the switching speed.

The major limiting factors are power and threshold voltage, tunneling leakage through gate oxide, lithography, short-channel effect, high-field effects, dopant number fluctuations, interconnect delays and electrostatic scale length. Both the standby power and the active power of a chip will increase precipitously below the 45nm technology generation.

Conventional scaling will no longer be sufficient to continue device performance by creating smaller MOSFET/CMOS, it will be running into fundamental barriers of physics. It is reported in [3] that the minimum MOSFET structure for a power supply voltage of 1.5V has a channel length of 0.52 μm and a gate oxide thickness of 9.4 nm. Difficult challenges lie ahead in tightening process tolerances to satisfy more stringent defect density and reliability requirements in future generation CMOS technologies. Thus, alternatives like SETs are being pursued.

1.2 Potential Nanoelectronics Devices and Application Areas

Single-electron tunneling (SET) devices have been proposed in [4] as one promising candidate for future nanoelectronic integrated circuits. SETs have appealing properties for implementing ultra-dense and complex signal and image processing systems. The potential for very dense arrays of SET transistors makes them attractive for the realization of **cellular non-linear network (CNN) circuits**, where locally-connected cells may alleviate the interconnect problem facing conventional architectures as they scale. In this paper, the use of nanoelectronic structures in CMOS-type digital circuits and in analog CNN architectures for potential application in future high-density and low-power CMOS-nanodevice hybrid circuits are investigated. The simple SET-CNN cell acts as a summing node that is capacitively coupled to the inputs and outputs of nearest neighbour cells.

SETs are also of increasing interest for their potential in room temperature application, high density memory and logic circuits with conventional silicon VLSI processing techniques because of its small size, low power consumption and high sensitivity.

It is reported in [7] that memory device is the most promising and lucrative application of SETs, which in principle could store one bit of information with one electron. Several companies have single-electron memory products in their roadmap for a planned release in the 2010 to 2015 time frame.

1.2.1 Single electron memory [6]

Scientists have long been endeavored to enhance the capacity of memory devices. If single electron memory can be realized, the memory capacity is possible to reach its utmost limit. SET can be used as memory cell since the state of Coulomb

island can be changed by the existence of one electron. Chou and Chan first pointed out the possibility of using SET as memories in which information is stored as the presence or absence of a single electron on the cluster. They fabricated a SET by embedding one or several nano Si powder in a thin insulating layer of SiO₂, then arranging the source and drain as well as gate around this Coulomb island. The read/write time of Chan's structure is about 20ns, lifetime is more than 10⁹ cycles, and retention time (during which the electron trapped in the island will not leak out) can be several days to several weeks.

These parameters would satisfy the standards of computer industry, so SET can be developed to be a candidate of basic computer units. If a SET stands for one bit, then an array of 4~7 SETs will be substantial to memorize different states. The properties of the memory unit composed of SETs are far more advantageous than that of CMOS. But the disadvantage is the practical difficulty in fabrication. When the time comes for the large scale integration of SETs to form logic gates, the full advantages of single electron memory will show. This is the threshold of quantum computing.

1.2.2 High sensitivity electrometer [6]

The most advanced practical application currently for SETs is probably the extremely precise solid-state electrometers (a device used to measure charge). The SET electrometer is operated by capacitively coupling the external charge source to be measured to the gate. Changes in the SET source-drain current are then measured. Since the amplification coefficient is very big, this device can be used to measure very small change of current.

Experiments showed that if there is a charge change of $e/2$ on the gate, the current through the Coulomb island is about 10⁹ e/sec. This sensitivity is many orders of magnitude better than common electrometers made by MOSFET. SETs have already been used in metrological applications as well as a tool for imaging

localized individual changes in semiconductors. Recent demonstration of single photon detection and RF operation of SETs make them exciting for new applications ranging from astronomy to quantum computer read-out circuitry.

The SET electrometer is in principle not limited to the detection of charge sites on a surface, but can also be applicable to a wide range of sensitive chemical signal transduction events as well. For example, the gate can be made coupling with some molecules, thus can measure other chemical properties during the process. However, as Lewis K M etc. pointed out, SETs electrometer must be designed with care. If the device under test has a large capacitance, it is not advantageous to use SETs as an electrometer. Since for a typical SET, $C_{SET} < 1 \mu\text{F}$, the suppression factor becomes unacceptable when the macroscopic device has a capacitance in the pF or nF range.

Therefore, SET amplifiers are not currently used for measuring real macroscopic devices. Other low-capacitance electrometers such as a recently proposed quantum point contact electrometer also suffer from a similar capacitance mismatch problem. But it is believed that if the capacitance mismatch can be solved efficiently, SETs may find many new ultra low-noise analog applications.

1.2.3 Microwave detection [6]

If a SET is attacked black body radiation, the photon-aided tunneling will affect the charge transfer of the system. Experiments show that the electric character of the system will be changed even by a tiny amount of radiation. The sensitivity of this equipment is about 100 times higher than the current best thermal radiation detector.

1.2.4 Application in the Metrology Area [7]

For metrology purposes one can accept setups with cryogenic temperatures allowing structures with dimensions in the tens of nanometers. Devices for precise current and capacitance measurements achieved by essentially counting electrons have been built successfully. These exhibit unprecedented accuracy over traditional methods. Super sensitive electrometers and the use of tunnel junction arrays as single-electron primary temperature sensors are very promising application. From an economical point of view metrology applications will hardly be noticed. But their development can provide important insight and fresh ideas for other single-electron application areas.

1.3 Theory of SET

The need for fast switching and lower power consumption is the main goal of semiconductor technology. Shrinkage in device dimensions raises switching frequencies and reduces power consumption. In sub-micron dimensions, quantum tunneling affects the MOSFET operation due to electron transport by tunneling from source to drain. Recently a new transistor was invented; the single electron transistor (SET) that operates on tunneling phenomena. This transistor turns on when one electron tunnels from source to drain. Figure 1.1 explains clearly the difference between SET and MOSFET.

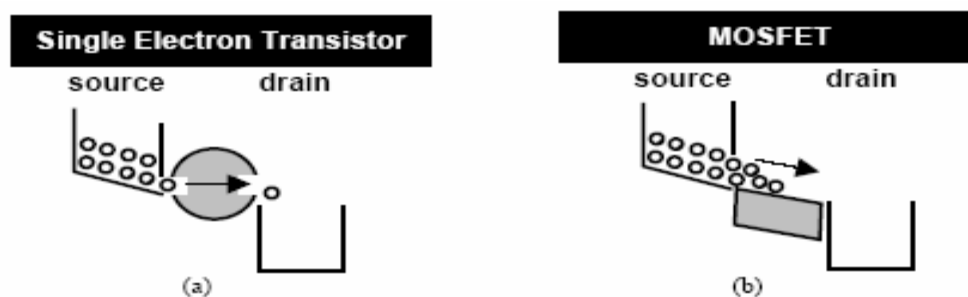


Figure 1.1: Transfer of electrons is (a) one-by-one in SET (b) conventional MOSFET where many electrons simultaneously participate to the drain current

The tunnel junction is the smallest unit cell of single electron transistor. It consists of two conductors separated by a thin insulator. Figure 1.2 shows the diagram of tunnel junction. The only way for electrons to move across the tunnel junction is to tunnel through. Although tunneling is a probability distribution function, electrons tunnel across the tunnel junction in a discrete manner.

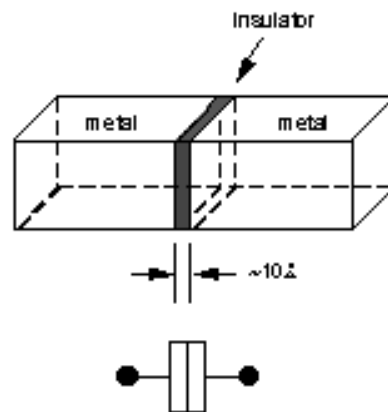


Figure 1.2: Tunnel junction consists of 2 metals that are separated by a thin insulator. Because of the separation, capacitance is formed and they are represented by capacitor value in the circuit.

Connecting two tunnel junctions together forms what is known as the Coulomb island, as this element is what we call as Single Electron Transistor (SET). This is shown by Figure 1.3.

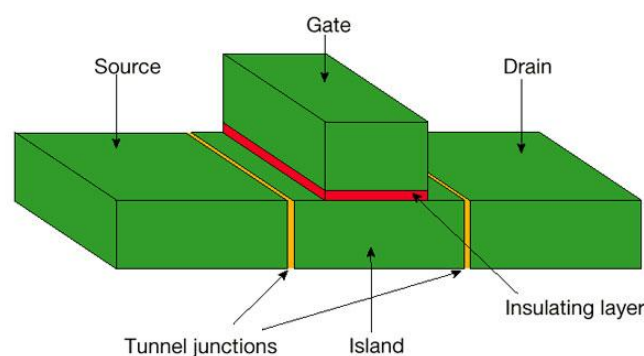


Figure 1.3: SET is type of switching device that uses controlled electron tunneling to amplify current

No electron can reside on the island unless its kinetic energy exceeds the Coulomb energy of the island, E_c , which is known as the Coulomb blockade.

$$E_c = \frac{e^2}{2C}$$

where, C is the total capacitance of the island. The island is capacitively coupled to the gate electrode by a thick insulating layer to prevent tunneling between the island and the gate. With zero voltage applied to the gate, the island's Coulomb energy blocks the current from drain to source until the drain-source voltage exceeds the threshold voltage, V_{th}

$$V_{th} = \frac{e}{C}$$

The gate voltage controls the charging energy of the island and consequently it controls the Coulomb blockade. Applying an appropriate value of gate voltage can thus eliminate the Coulomb blockade.

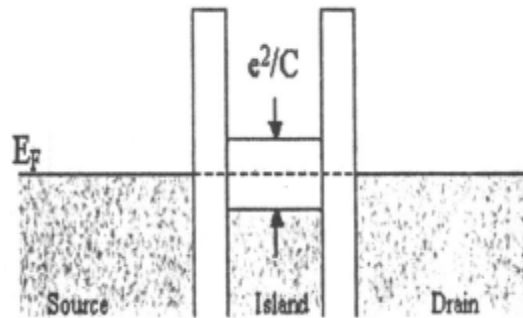


Figure 1.4: Energy level diagram

Single electron transistor operation can be explained by the orthodox theory. In this theory the tunneling rate across each tunnel junction of the transistor is calculated. The tunnel rate is derived from the Fermi golden rule taking into consideration the change in free energy of the system. The free energy is equivalent to the energy change caused by a tunnel event in the orthodox theory. The Fermi golden rule states that the transition rate (tunnel rate) is highest when the change in free energy before and after the tunnel event is minimal. The change in free energy is the difference between the electrostatic energy of the system and the work done by voltage sources before and after the tunnel event.

The change in free energy can be simply derived by the method of critical voltage.

Utilizing the orthodox theory with statistical mechanics develops the master equation. It computes the time dependent occupation for each state in the system. The drain-source current of the transistor is computed using the results of the master equation. [5]

1.4 History of SET

The effects of charge quantization were first observed in tunnel junctions containing metal particles as early as 1968. Later, the idea that the Coulomb blockade can be overcome with a gate electrode was proposed by a number of authors, and Kulik and Shekhter developed the theory of Coulomb-blockade oscillations, the periodic variation of conductance as a function of gate voltage. Their theory was classical, including charge quantization but not energy quantization. However, it was not until 1987 that Fulton and Dolan made the first SET, entirely out of metals, and observed the predicted oscillations. They made a metal particle connected to two metal leads by tunnel junctions, all on top of an insulator with a gate electrode underneath. Since then, the capacitances of such metal SETs have been reduced to produce very precise charge quantization. The first semiconductor SET was fabricated accidentally in 1989 by Scott-Thomaset in narrow Si field effect transistors. In this case the tunnel barriers were produced by interface charges.

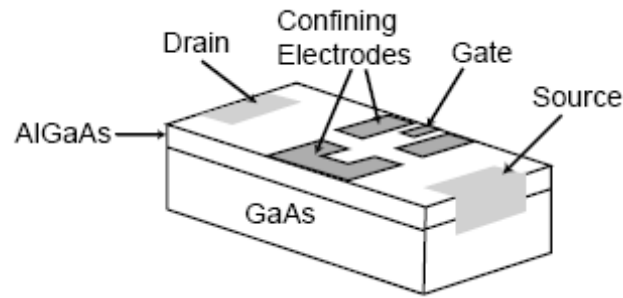


Figure 1.5: Schematic drawing of a SET. Wires are connected to source and drain contacts to pass current through the 2DEG at the GaAs/AlGaAs interface. Wires are also connected to the confining electrodes to bias them negatively and to the gate electrode that controls the electrostatic energy of the confined electrons.

Shortly thereafter Meirav et al. made controlled devices of the kind depicted in Fig. 1.5, even though with an unusual heterostructure with AlGaAs on the bottom instead of the top. In these and similar devices the effects of energy quantization were easily observed. Only in the past few years have metal SETs been made small enough to observe energy quantization. Foxman et al. also measured the level width Γ and showed how the energy and charge quantization are lost as the resistance decreases toward h/e^2 . In most cases the potential confining the electrons in a SET is of sufficiently low symmetry that one is in the regime of quantum chaos: the only quantity that is quantized is the energy. In this case there is a very sophisticated approach, based in part on random matrix theory, for predicting the distributions of peak spacings and peak heights for data. There are challenging problems in this arena that are still unsolved. In particular, there is great interest in how the interplay of exchange and level spacing determines the spin of a small metal SET. Another way to eliminate the scattering that destroys angular momentum conservation is to apply a magnetic field perpendicular to the 2DEG. At sufficiently M. A. Kastner, Single electron transistor and artificial atoms 893 high fields elegant patterns are seen in the single-electron-peak positions as a function of field. The evolution of Coulomb charging peaks with magnetic field have been interpreted with various degrees of sophistication, imitating the development of the theory of atoms. First one tries the “constant interaction model” in which electrons are treated as independent

except for a constant Coulomb charging energy. This gives only a qualitative picture of the physics. In order to be quantitative, one needs to at least treat the electron-electron interactions self-consistently (analogous to the Thomas-Fermi model), and for some cases one needs to include exchange and correlations. In particular, it is found that electrons in an SET undergo a series of phase transitions at high magnetic field. One of these is well described by Hartree-Fock theory, but others appear to require additional correlations. [5]

1.5 Types of SETS [8]

Single-electron transistors can be made using metals, semiconductors, carbon nanotubes, or single molecules. **Aluminum SET's** made with Al/AlO_x/Al tunnel junctions are the SET's that have been used most often in applications. This kind of SET is used in metrology to measure currents, capacitance, and charge. They are used in astronomical measurements and they have been used to make primary thermometers. However, many fundamental single-electron measurements have been made using GaAs heterostructures. The island of this kind of SET is often called a quantum dot. Quantum dots have been very important in contributing to our understanding of single-electron effects because it is possible to have just one or a few conduction electrons on a quantum dot. The quantum states that the electrons occupy are similar to electron states in an atom and quantum dots are therefore sometimes called artificial atoms. The energy necessary to add an electron to a quantum dot depends not just on the electrostatic energy of Eq. 2 but also on the quantum confinement energy and the magnetic energy associated with the spin of the electron states. By measuring the current that flows thorough a quantum dot as a function of the gate voltage, magnetic field, and temperature allows one understand the quantum states of the dot in quite some detail.

The SET's described so far are all relatively large and have to be measured at low temperature, typically below 100 mK. For higher temperature operation, the SET's have to be made smaller. Ono et al. [9] used a technique called pattern

dependent oxidation (PADOX) to make small **silicon SET's**. These SET's had junction capacitances of about 1 aF and a charging energy of 20 meV. The silicon SET's have the distinction of being the smallest SET's that have been incorporated into circuits involving more than one transistor.

Specifically, Ono et al. constructed an inverter that operated at 27 K. Postma et al. [10] made a SET that operates at room temperature by using an AFM to buckle a metallic **carbon nanotube** in two places. The tube buckles much the same way as a drinking straw buckles when it is bent too far. Using this technique, a 25 nm section of the nanotube between the buckles was used as the island of the SET and a conducting substrate was used as the gate. The total capacitance achievable in this case is also about 1 aF.

Pashkin et al. [11] used **e-beam lithography** to fabricate a SET with an aluminum island that had a diameter of only 2 nm. This SET had junction capacitances of 0.7 aF, a charging energy of 115 meV, and operated at room temperature.

SET's have also been made by placing just a single molecule between closely spaced electrodes. Park et al. [12] built a SET by placing a C60 molecule between electrodes spaced 1.4 nm apart. The total capacitance of the C60 molecule in this configuration was about 0.3 aF. **Individual molecules** containing a Co ion bonded to polypyridyl ligands were also placed between electrodes only 1-2 nm apart to fabricate a SET. [14] In similar work, Liang et al. [13] placed a single divanadium molecule between closely spaced electrodes to make a SET. In the last two experiments, the Kondo effect was observed as well as the Coulomb blockade. The charging energy in the molecular devices was above 100 meV.

One of the conclusions that can be drawn from this review of SET devices is that small SET's can be made out of a variety of materials. Single electron transistors with a total capacitance of about 1 aF were made with aluminum, silicon, carbon nanotubes and individual molecules. It seems unlikely that SET's with capacitances smaller than the capacitances of the molecular devices can be made. This sets a

lower limit on the smallest capacitances that can be achieved at about 0.1 aF. Achieving small capacitances such as this has been a goal of many groups working on SET's. However, while some of the device characteristics improve as a SET is made smaller, some of the device characteristics get worse as SET's are made smaller. For some applications, the single molecule SET's are too small to be useful.

As SET's are made smaller, there is an increase in the operating temperature, the operating frequency, and the device packing density. These are desirable consequences of the shrinking of SET devices. The undesirable consequences of the shrinking of SET's are that the electric fields increase, the current densities increase, the operating voltage increases, the energy dissipated per switching event increases, and the power dissipated per unit area increases, the voltage gain decreases, the charge gain decreases, and the number of Coulomb oscillations that can be observed decrease.

The future of research on SETs looks very bright. There are strong efforts around the world to make the artificial atoms in SETs smaller, in order to raise the temperature at which charge quantization can be observed. These involve self-assembly techniques and novel lithographic and oxidation methods whereby artificial atoms can be made nearly as small as natural ones. This is, of course, driven by an interest in using SETs for practical applications. However, as SETs get smaller, all of their energy scales can be larger, so it is very likely that new phenomena will emerge. [5]

1.6 Objectives of the project

- To study nanoelectronics devices in particular SET
- To simulate Single Electron Transistor (SET) circuits using Monte Carlo method
- To study functions of MOSES in simulating SET circuits.

1.7 Scope of the project

Due to the time constraint of Project 1 and 2, three SET circuits: Array, SET and Junction circuits are simulated. The areas of the simulation are mainly on IV curve, Spectral densities and Energies, and observations are made on the circuit behaviour when the value of capacitance and temperature change.

1.8 Motivations

SET is of increasing interest not only from the fundamental point of view but also for their potential room-temperature application to very high density memory and logic circuits with conventional silicon VLSI processing techniques. As in the case of the conventional CMOS circuit design, the modeling of devices and the simulation of the circuit would be a key step to design the SET circuits. In the case of the conventional circuit, the compact simulators such as MOSES are used to simulate the characteristics of the given circuit topology.

1.9 Methodology and Report Structure

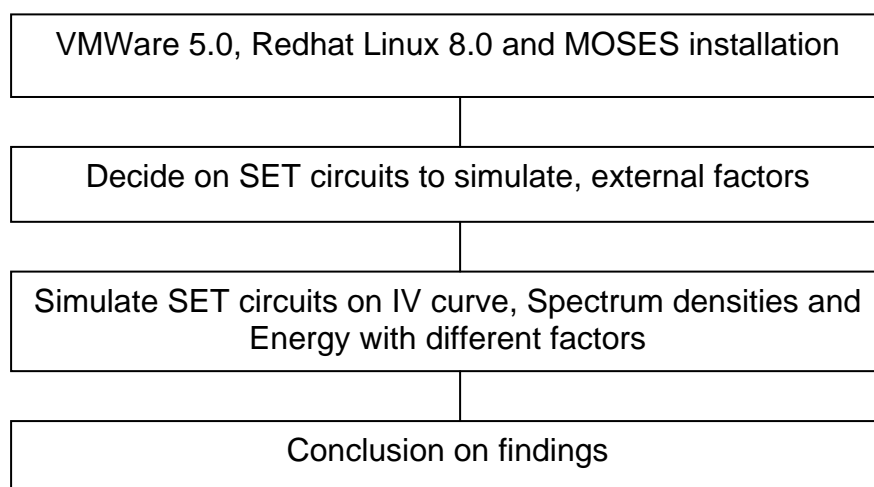


Figure 1.6: Flowchart on Project Methodology

Prior to MOSES installation, having Linux installed in the system is compulsory since it only runs on Linux environment. Since there is no budget to have dedicated PC to run specifically on Linux, I have decided to turn my PC to run two operating systems by installing VMWare. VMWare, as its name stands for Virtual Machine allows more than one operating system to run on the same machine. Figure 1.7 shows Linux in Windows environment using VMWare.

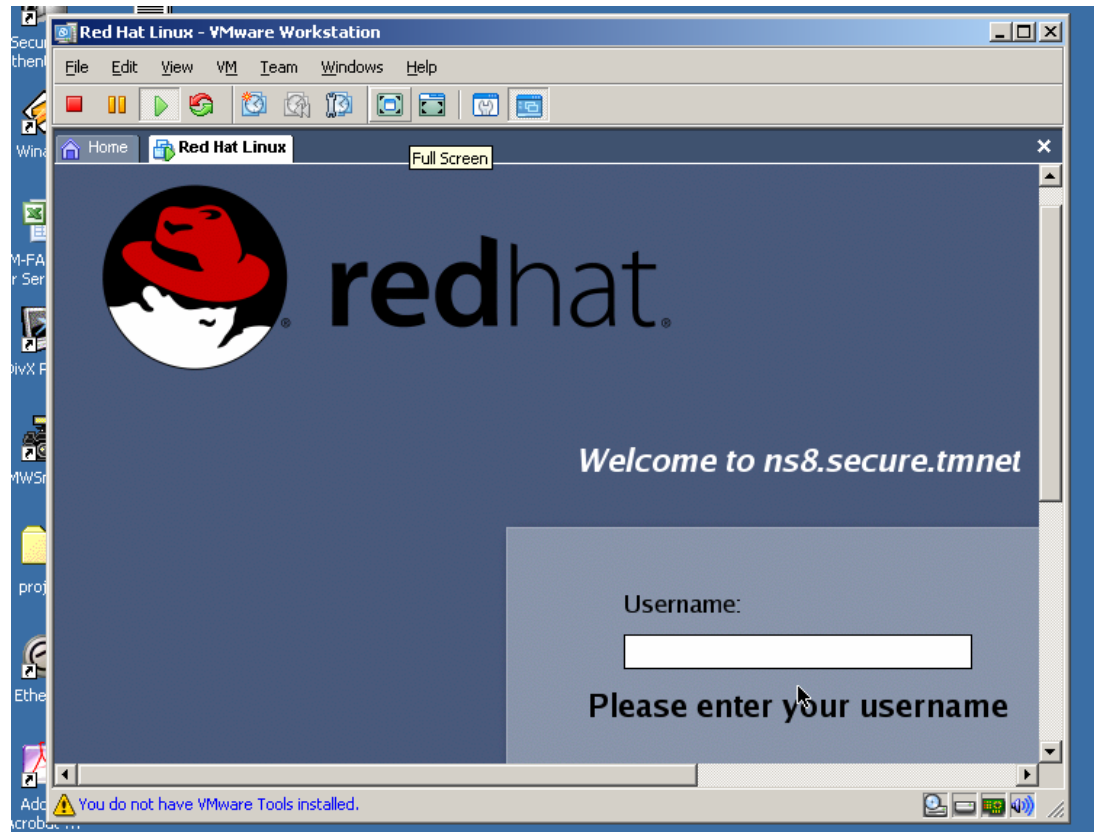
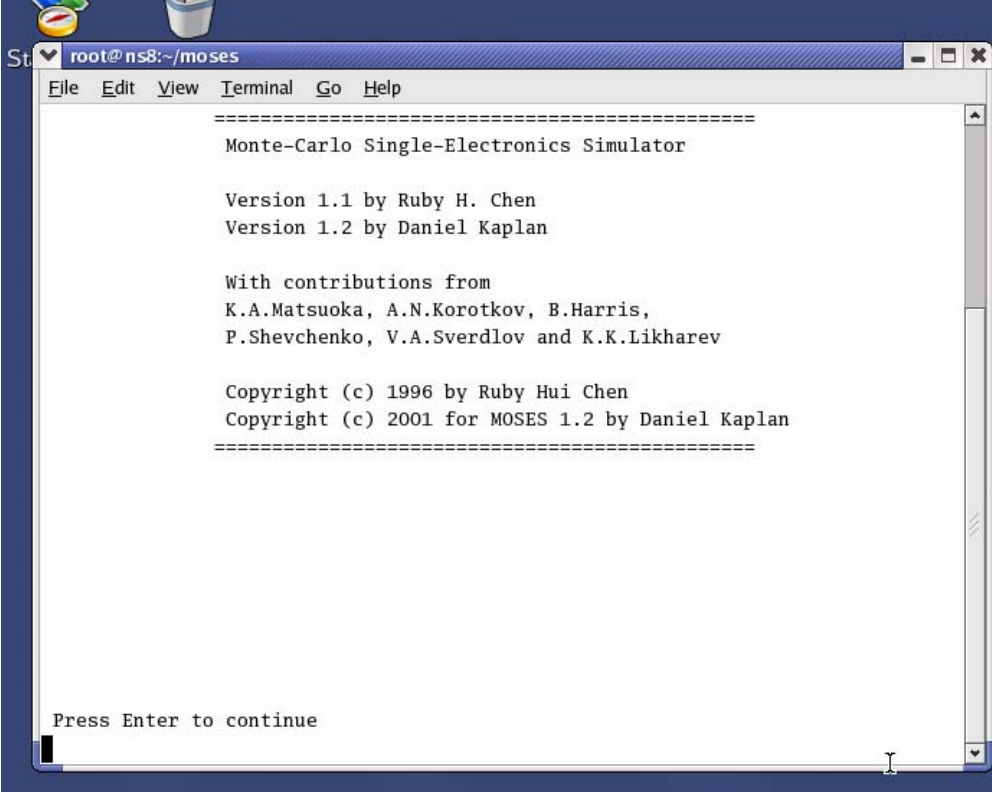


Figure 1.7: By using VMWare, it is possible to have more than one OS in the same machine

After installing VMWare, Linux and MOSES, it is time to decide on what types of SET circuits to be simulated. For this purpose three SET circuits have been finalized: Array, SET and Junction circuits. These circuits are selected since there are varieties on IV curve, Spectrum densities and Energy results among them.



```
root@ns8:~/moses
File Edit View Terminal Go Help
=====
Monte-Carlo Single-Electronics Simulator

Version 1.1 by Ruby H. Chen
Version 1.2 by Daniel Kaplan

With contributions from
K.A.Matsuoka, A.N.Korotkov, B.Harris,
P.Shevchenko, V.A.Sverdlov and K.K.Likharev

Copyright (c) 1996 by Ruby Hui Chen
Copyright (c) 2001 for MOSES 1.2 by Daniel Kaplan
=====

Press Enter to continue
```

Figure 1.8: MOSES in Linux environment

After the raw results are displayed, they are then transferred to Microsoft excel for graph plotting, since this function is having problem in MOSES application.

Finally, there is a discussion on what have the result shown based on comparison with current SET research community, especially from IEEE Xplore on the net.